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PATENT APPLICATION

RESPONSE UNDER 37 CFR §1.116
EXPEDITED PROCEDURE
TECHNOLOGY CENTER ART UNIT 2813

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Akira SHIMOKOHBE et al.

Application No.: 09/556,795

Filed: April 25, 2000

For: A THIN FILM-STRUCTURE AND A METHOD FOR PRODUCING THE SAME

Group Art Unit: 2813 2829

Examiner: Asok K. Sarkar

Docket No.: 106096

TECHNOLOGY CENTER 2800

JAN 28 2002

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AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Office Action mailed November 30, 2001, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claim 3 as follows:

~~3.~~ (Twice Amended) A method for producing a thin film-structure comprising the steps of:

forming on a substrate a thin film made of an amorphous material having a supercooled liquid phase region,

heating the thin film to a temperature within the supercooled liquid phase region so that the thin film has a viscous flow between 10^8 - 10^{13} Pa·s and thereby deforming the thin film to a given shape without the use of an external force, and

~~Sub E1~~